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(54) PIPING AND SYSTEM FOR FEEDING
SUPERHIGH PURITY GAS AND PURE WATER
AND PROCESS DEVICE THEREFOR

(57) Abstract

PURPOSE: To prevent the contamination of a semiconductor device, etc., into which gas is introduced through a gas feeding system, perfectly preventing the adhesion of Mn inside the gas feeding system, in the vicinity of the surface of a welded part.

CONSTITUTION: A part of a pipe which is to be welded is made of the austenitic stainless steel containing manganese in 0.03wt.% or less. In this system, the adhesion of Mn in the vicinity of a welded part immediately after welding is prevented perfectly, and the erosionproofness is excellent. A process device is characterized that the welded part is made of the austenitic stainless steel containing manganese in 0.03% or less, and the adhesion of Mn in the vicinity of the welded part in the state immediately after welding is perfectly prevented, and the high erosionproofness is provided. The following component: Cr 17.0-18.0wt% and Ni 14.0-15.0wt% is preferable.

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